Gar&/J. Derderian et al.

Title:

Atomic Layer Deposition Methods, and Methods of Forming

**Materials Over Semiconductor Substrates** 

Assignee:

Micron Technology, Inc.

Serial No.: 10/671,922

Filed:

September 24, 2003 [RCE Filed Herewith]

## **INFORMATION DISCLOSURE STATEMENT**

## PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

The attached Form PTO-1449 is submitted in compliance with 37 CFR §1.56. Pursuant to Federal Register, Vol. 69, No. 182, pg. 56542. (September 21, 2004), no copies of any cited U.S. patents or U.S. published applications are included herewith. No admission is made regarding whether the listed reference is prior art.

By:

Citation of this patent is respectfully requested.

Respectfully submitted,

David G. Latwesen, Ph.D.

Reg. No. 38,533

Wells St. John P.S.

EV633261929

Form PTO-1449

## U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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LIST OF ART CITED BY APPLIC

ATTY. DOCKET NO. MI22-2296

SERIAL NO. 10/671,922

APPLICANT

Garo J. Derderian et al.

FILING DATE Sept. 24, 2003 [RCE filed herewith] GROUP 2812

## U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filir If App	ng Date propriate
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